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Title: Detector useful in image sensor for detecting terahertz radiation, comprises micro-plasma cell with cavity, and read-out electronics connected to cell to measure changes electron density with respect to bias provided electron density

Inventor Name(s): MEIJER A S; VAN DER ZANDE W J

Patent Assignee(s): UNIV STICHTING KATHOLIEKE (UYKA-Non-standard)

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Abstract: NOVELTY - The detector comprises a micro-plasma cell (1) with a cavity (5) comprising a plasma in operation when applying a bias to the micro-plasma cell, read-out electronics (20) connected to the micro-plasma cell for measuring changes an electron density in the plasma in the micro-plasma cell with respect to bias provided electron density, and a radiation source for irradiating the plasma in the micro-plasma cell. The cavity comprises a gas composition near atmospheric pressure or higher, where the gas composition comprises a Penning mixture.

USE - The detector is useful in an image sensor for detecting terahertz radiation (claimed), where the sensor is useful for industrial applications including product inspection on conveyor-belts, medicine, communication, homeland security and space technology.

ADVANTAGE - The detector is capable efficiently and economically detecting the terahertz radiation with high sensitivity and signal-to-noise ratio.

DETAILED DESCRIPTION - The detector comprises a micro-plasma cell (1) with a cavity (5) comprising a plasma in operation when applying a bias to the micro-plasma cell, read-out electronics (20) connected to the micro-plasma cell for measuring changes an electron density in the plasma in the micro-plasma cell with respect to bias provided electron density, and a radiation source for irradiating the plasma in the micro-plasma cell. The cavity comprises a gas composition near atmospheric pressure or higher, where the gas composition comprises a Penning mixture. The Penning mixture comprises a main inert gas, and a quench gas having a lower ionization potential than the main inert gas. The micro-plasma cell comprises a first electrode, a second electrode (4), and a substrate provided with a thin film first electrode, a dielectric layer and a conductive second electrode layer, where the first electrode is a tuned electrode. The tuned electrode comprises: a metamaterial, which forms a periodic structure that compromises highly conductive materials and/or shaped metals such as graphene, gold or copper; split ring resonators; and metamaterial structures with layers stacked on top each other and spaced by a dielectric. The periodic structure has structural features that are smaller than a wavelength terahertz radiation. The electrodes are grouped into a single image pixel, and are isolated from the cavity. The micro-plasma cell is driven by a direct current bias and an alternating current bias unit, and the read-out electronics comprise direct current-bias decoupling components and a network analyzer. The dielectric layer is provided with an aperture above the thin film first electrode. The conductive second electrode layer comprises apertures above the cavity, and a material transparent to radiation having a wavelength 50-3000  $\mu$  m. INDEPENDENT CLAIMS are included for:

- (1) a method detecting terahertz radiation; and
- (2) an image sensor.

DESCRIPTION DRAWING(S) - The diagram shows a schematic view a detector.

Micro-plasma cell (1)

Insulating material (3)

Second electrode (4)

Cavity (5)

Read-out electronics. (20)

Drawing:

Derwent Class Code(s): U13 (Integrated Circuits); V05 (Valves, Discharge Tubes and CRTs)

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